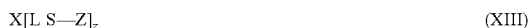


a compound having a functional group selected from the group consisting of a propargyl carbonate, a propargyl carbamate, a propargyl ether, a propargyl ester, a butynyl carbonate, a butynyl carbamate, a butynyl ether, a butynyl ester, a pentynyl carbonate, a pentynyl carbamate, a pentynyl ether, and a pentynyl ester; and/or one terminal alkyne functional group or at least two terminal alkyne functional groups.

74. The resin composition according to claim **71**, wherein the at least one compound C2 is represented by the following general formula (XIII):



wherein

z represents an integer of from 2 to 1000;

Z represents—independently from each other on each occurrence—hydrogen or a thiol protecting group;

L represents—independently from each other on each occurrence—a single bond or a divalent group selected from the group consisting of a linear or branched, saturated or unsaturated, substituted or unsubstituted alkylene group; a linear or branched, saturated or unsaturated, substituted or unsubstituted heteroalkylene group; a saturated or unsaturated, substituted or unsubstituted cycloalkylene group; a saturated or unsaturated, substituted or unsubstituted heterocycloalkylene group; a substituted or unsubstituted arylene group; a substituted or unsubstituted heteroarylene group; a linear or branched, substituted or unsubstituted aralkylene group; a linear or branched, substituted or unsubstituted alkarylene group; or a silicium containing divalent group; and

X represents a z-valent group selected from the group consisting of a linear or branched, saturated or unsaturated, substituted or unsubstituted alkyl group; a linear or branched, saturated or unsaturated, substituted or unsubstituted heteroalkyl group; a saturated or unsaturated, substituted or unsubstituted cycloalkyl group; a saturated or unsaturated, substituted or unsubstituted heterocycloalkyl group; a substituted or unsubstituted aryl group; a substituted or unsubstituted heteroaryl group; a linear or branched, substituted or unsubstituted aralkyl group; a linear or branched, substituted or unsubstituted alkaryl group; or a silicium containing z-valent group.

75. The composition according to claim **71**, wherein the at least one compound C3 comprises at least one of the following features:

at least one functional group selected from the group consisting of a vinyl functional group, an allyl functional group, an acrylate functional group and a methacrylate functional group; and/or

at least two carbon-carbon double bonds.

76. The composition according to claim **71**, wherein the composition comprises at least two compounds C3 including a compound C3a having at least one methacrylate functional group and a compound C3b having at least one allyl functional group, in particular wherein the compound C3b further has at least one of a carbamate group and an isocyanurate group.

77. The composition according to claim **71**, wherein the at least one stabilizer comprises at least one radical scavenger, in particular at least one phenolic radical scavenger.

78. The composition according to claim **71**, wherein the at least one stabilizer comprises at least one phosphorous containing compound, in particular at least one phosphonic acid and/or at least one phosphoric acid and/or a derivative thereof.

79. The composition according to claim **71**, wherein the at least one stabilizer comprises at least one complexing agent, in particular at least one aromatic azo compound.

80. The composition according to claim **71**, wherein the at least one stabilizer comprises at least one aromatic azo compound having a hydroxy group in ortho-position with regard to an azo group.

81. The composition according to claim **71**, wherein the at least one stabilizer comprises:

at least one radical scavenger, in particular at least one phenolic radical scavenger, and

at least one phosphorous containing compound, in particular at least one phosphonic acid and/or at least one phosphoric acid and/or a derivative thereof.

82. The composition according to claim **71**, wherein the at least one stabilizer comprises:

at least one radical scavenger, in particular at least one phenolic radical scavenger, and

at least one complexing agent, in particular at least one aromatic azo compound.

83. The composition according to claim **71**, wherein the at least one stabilizer comprises:

at least one radical scavenger, in particular at least one phenolic radical scavenger,

at least one phosphorous containing compound, in particular at least one phosphonic acid and/or at least one phosphoric acid and/or a derivative thereof, and

at least one complexing agent, in particular at least one aromatic azo compound.

84. The composition according to claim **71**, further comprising at least one photoinitiator, in particular an ultraviolet-active photoinitiator and/or a visible light-active photoinitiator.

85. The composition according to claim **71**, wherein the composition comprises at least one of the following features: the composition comprises from 0.001 to 10 wt.-% of the at least one stabilizer; and/or

the composition further comprises at least one additive selected from the group consisting of a pigment, an inorganic filler, an organic filler, a dispersing agent, a levelling agent, a slip agent, a light absorber, a rheology modifier and a defoaming additive; and/or

the composition is substantially solvent-free, in particular substantially water-free.

86. A kit comprising

at least one compound C1 having at least one terminal alkyne functional group and/or at least one compound C3 having at least one carbon-carbon double bond

at least one compound C2 having at least two thiol functional groups; and

at least one stabilizer selected from the group consisting of a radical scavenger, a phosphorous containing compound and a complexing agent.

87. rising the steps of

providing a resin composition as defined in claim **71**, the resin composition further comprising at least one photoinitiator; and

irradiating at least a part of the resin composition with an energy-carrying activation beam so as to cause polym-